

AMENDMENTS TO THE CLAIMS

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Claim 1 (currently amended): A wafer processing system comprising:  
a load-lock having only one pedestal configured to support a single wafer thereon  
~~support for accommodating only a single wafer at a time~~, the load-lock having an integral  
cooling unit for cooling a the single wafer;  
a transport module having a load chamber, a transfer chamber, and a pass-through  
chamber located between the load chamber and the transfer chamber, the load chamber  
being coupled to the load lock;  
an intermediate process module coupled to the load chamber and the transfer  
chamber;  
a first set of process modules coupled to the load chamber; and  
a second set of process modules coupled to the transfer chamber.

Claim 2 (original): The system of claim 1 wherein a process module in the first set of  
process modules includes a pre-clean module.

Claim 3 (original): The system of claim 1 wherein a process module in the first set of  
process modules includes a physical vapor deposition module.

Claim 4 (original): The system of claim 1 wherein a process module in the first set of  
process modules includes a chemical vapor deposition module.

Claim 5 (original): The system of claim 1 wherein a process module in the second set of  
process modules includes a pre-clean module.

Claim 6 (original): The system of claim 1 wherein a process module in the second set of  
process modules includes a chemical vapor deposition module.

Claim 7 (original): The system of claim 1 wherein a process module in the second set of  
process modules includes a physical vapor deposition module.

Claim 8 (cancelled)

Claim 9 (original): The system of claim 1 wherein the intermediate process module is  
configured as a degas module.

Claim 10 (original): The system of claim 1 wherein the pass-through chamber is  
configured as a cooling station.

Claim 11 (original): The system of claim 1 wherein the intermediate process module is  
configured as a pre-clean module.

Claim 12 (original): The system of claim 1 wherein the intermediate process module is configured as a PVD module.

Claim 13 (original): The system of claim 1 wherein the intermediate process module is configured as a CVD module.

Claims 14-16 (cancelled)

Claim 17 (currently amended) A wafer processing system comprising:  
a load lock having only ~~a single wafer support~~ one pedestal for supporting a wafer thereon, the ~~single wafer support~~ pedestal having an integral cooling unit for cooling a wafer;  
a transport module having a first chamber, a second chamber, and a pass-through chamber between the first chamber and the second chamber, the first chamber being coupled to the load lock;  
an intermediate process module coupled to the first chamber;  
a process module coupled to the first chamber; and  
another process module coupled to the second chamber.

Claim 18 (cancelled)

Claim 19 (currently amended): The system of claim 17 wherein the ~~single wafer support pedestal~~ pedestal is a water-cooled.

Claim 20 (original): The system of claim 17 wherein the intermediate process module is also coupled to the second chamber.

Claim 21 (original): The system of claim 17 wherein the pass-through chamber is configured as a cooling station.

Claims 22-24 (cancelled)